

FORM PTO-1449 INFORMATION DISCLOSURE CITATIONS IN AN APPLICATION	Atty Docket:	02-6392/1D	Serial #: 10/802522
	Applicant:	Sukharev, Catabay, Lu	
	Filing Date:	2004.03.17	Group: 2815

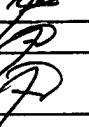
U.S. PATENT DOCUMENTS

Examiner Initial	Cite #	Document Number	Date	Name	Class	Sub-Class	Filing Date
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FOREIGN PATENT DOCUMENTS

Examiner Initial	Cite #	Document Number	Date	Country	Class	Sub-Class	Translation
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OTHER NON-PATENT DOCUMENTS

Examiner Initial	Cite #	Author, title, date, pertinent pages, etc.
	1	Hu et al., <i>Chemical vapor deposition copper interconnections and electromigration</i> , Electrochemical Society Proceedings, 97-25, 1514 (1997).
	2	Hu et al., <i>Applied Physics Letters</i> , Vol. 74, Number 20, pp. 2945-2947 (1999).
	3	Wang et al., <i>Stress-free polishing advances copper integration with ultralow-k dielectrics</i> , Solid State Technology, pp. 101-106, October 2001.

Examiner 	Date Considered: <u>5/28/05</u>
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.	

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